Strain-engineered electronic, valley, and photocatalytic properties in Janus WSiGe Z_4 (Z = N, P, As) monolayers

Ming-Yang Liu1*, Yao He2, Xuan Li3, and Kai Xiong4

¹Department of Physics and Electronic Science, Chuxiong Normal University, Chuxiong 675000, P. R.

China

²Department of Physics, Yunnan University, Kunming 650091, P. R. China

³College of Physics and Information Engineering, Zhaotong University, Zhaotong 657000, P. R. China

⁴Materials Genome Institute, School of Materials and Energy, Yunnan University, Kunming 650091, P.

R. China

*Corresponding author: Ming-Yang Liu (E-mail: 18788549890@163.com)



FIG. S1(a) Phonon spectrum of Janus WSiGeZ₄ monolayers.



FIG. S2 Side views of Janus WSiGe Z_4 monolayers after AIMD simulations at T = 500 K.



FIG. S3 The 2D Young's modulus of Janus WSiGeZ₄ monolayers.



FIG. S4 The band structures of WSi_2Z_4 and WGe_2Z_4 without (red line) and with (blue line) SOC using PBE functional.



FIG. S5 The band gap (a) and (b) band structure of WSiGeN₄ with U_{eff} .



FIG. S7 The orbital projected band structure of WSiGeP₄ with SOC using PBE functional. The Fermi level is set at the zero energy and the size of symbol is proportional to the orbital weight.



FIG. S8 The orbital projected band structure of WSiGeAs₄ with SOC using PBE functional. The Fermi level is set at the zero energy and the size of symbol is proportional to the orbital weight.



FIG. S9 The band gap of Janus WSiGeZ₄ monolayers with external electric field.



FIG. S10 Band edge alignment for water redox reactions of (a) WSiGeP₄ and (b) WSiGeAs₄ with strain at Ph=0 and 7.



FIG. S11 Phonon spectrum of the strained Janus $WSiGeZ_4$ monolayers.